

**LISTING OF CLAIMS**

Claims 1-25 (Canceled).

26. (Previously Presented) A plasma etching composition comprising:  
  
at least two fluorocarbons and ammonia, wherein said at least two fluorocarbons and said ammonia form a reactive mixture, and  
  
wherein said at least two fluorocarbons are selected from the group consisting of fluorohydrocarbons, chlorofluorocarbons, and chlorofluorohydrocarbons.

Claims 27-76 (Canceled).

77. (Previously Presented) A plasma etching composition comprising:  
  
at least one fluorocarbon, oxygen, and ammonia, wherein said at least one fluorocarbon, said oxygen, and said ammonia form a reactive mixture.

78. (Previously Presented) A plasma etching composition comprising:  
  
at least two fluorocarbons and ammonia, wherein said at least two fluorocarbons and said ammonia form a reactive mixture, and  
  
wherein at least one of said at least two fluorocarbons are selected from the group consisting of C<sub>4</sub>F<sub>8</sub>, C<sub>4</sub>F<sub>6</sub>, C<sub>5</sub>F<sub>8</sub>, C<sub>3</sub>F<sub>8</sub>, and CH<sub>2</sub>F<sub>2</sub>.

79. (Previously Presented) The composition of claim 78, wherein at least one of said at least two fluorocarbons is CH<sub>2</sub>F<sub>2</sub>.

80. (Previously Presented) The composition of claim 79, wherein said at least two fluorocarbons are CF<sub>4</sub>, CHF<sub>3</sub>, and CH<sub>2</sub>F<sub>2</sub>.

81. (Previously Presented) The composition of claim 78, further comprising:

at least one of oxygen and nitrogen.

82. (Previously Presented) The composition of claim 26, further comprising:

at least one of oxygen and nitrogen.